

## ECE G287 Optical Detectors Problem Set 2

1. Beginning from the definition that  $p = \int_{-\infty}^{E_v} (1 - f(E)) N(E) dE$  and assuming a parabolic isotropic hole band  $E = (\hbar k)^2 / 2m^*$  show that

$$p = 2 \left( \frac{2\pi m^* kT}{\hbar^2} \right)^{3/2} e^{-(E_f - E_v)/kT}$$

if it is assumed that  $E_f - E_v \gg kT$  for all the states in the valence band.

2. Find an expression for  $N(E)$  (= number of electron states between  $E$  and  $E + dE$ ) for the conduction band in silicon that has 6 pockets, each described by a longitudinal mass of  $m_l = 0.98 m_o$  and a transverse mass of  $m_t = 0.19 m_o$  ( $m_o$  = free electron mass =  $9.11 \times 10^{-31}$  kg.), so that:

$$E = \frac{(\hbar k_z)^2}{2m_l} + \frac{(\hbar k_x)^2}{2m_t} + \frac{(\hbar k_y)^2}{2m_t}$$

Then show that for  $E_c - E_f \gg kT$  the density of electrons in the conduction band can be given by

$$n = 2 \left( \frac{2\pi m_d^* kT}{\hbar^2} \right)^{3/2} e^{-(E_c - E_f)/kT}$$

and find a value for  $m_d^*$ .

3. Consider a sample of silicon that has  $N_d = 3 \times 10^{17} \text{ cm}^{-3}$  phosphorus donors located at  $E_d = E_c - 44 \text{ meV}$  (44 meV below the conduction band edge). The energy gap is  $E_c - E_v = 1.11 \text{ eV}$ . Assume the electron density of states mass =  $1.1 m_o$  and a hole density of states mass =  $0.55 m_o$  and you can assume that  $(E_c - E_f)$  and  $(E_f - E_v) \gg kT$ . The number of electrons excited from the donor level is equal to the density of ionized donor states  $N_d^+ = N_d (1 - f(E_d))$ . By numerically solving for the condition that  $n = N_d^+ + p$ , find the position of the Fermi level  $E_f$  for  $T = 4.2 \text{ K}$ ,  $77 \text{ K}$ ,  $300 \text{ K}$ , and  $600 \text{ K}$ . What percentage of the donor states are ionized at each temperature? Is the condition that  $(E_c - E_f)$  and  $(E_f - E_v) \gg kT$  satisfied at each temperature.

4. Assuming an abrupt junction with  $N_d$  density of donors on the n-side and  $N_a$  density of acceptors on the p-side, derive expressions for the depletion region width  $W(V_a)$  and the junction capacitance  $C(V_a)$  as a function of applied voltage  $V_a$ . Compare your expression for  $C(V_a)$  with a simple expression that you would get assuming a simple parallel-plate capacitor with the depletion charge separated by  $W(V_a)$ .

5. Consider a two-dimensional electron gas in a GaAs heterostructure that consists of a single layer of GaAs of thickness  $d$  between two layers of GaAlAs. The electron energy bands of the conduction band electrons trapped in the “quantum well” between the two GaAlAs layers are given by:

$E = E_c + E_n + \frac{(\hbar k_x)^2}{2m^*} + \frac{(\hbar k_y)^2}{2m^*}$  where  $E_c$  is the conduction band edge and  $E_n = \frac{\hbar^2}{2m^*} (n\pi/d)^2$  ( $n$  is any positive integer,  $n=1, 2, 3, \dots$ ).

Plot the energy of the bands for  $n=1, 2$ , and  $3$  vs.  $k_t = \sqrt{k_x^2 + k_y^2}$  assuming that the thickness of the GaAs layer is  $d=150 \text{ \AA}$  and the effective mass of the conduction band in GaAs is  $m^*=0.067 m_0$ . Plot the bands from  $E=E_c$  to  $E_c+300 \text{ meV}$ . (You can set the energy of the conduction band edge  $E_c=0$ .)

Find an expression for the density of states  $N(E)$  where  $N(E)dE$  is the number of electron states between  $E$  and  $E + dE$  and plot  $N(E)$  vs.  $0 < E < 300 \text{ meV}$  for the  $150 \text{ \AA}$  GaAs quantum well described above.